

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 10-211434  
(43)Date of publication of application : 11.08.1998

(51)Int.Cl. B01J 39/18  
B01J 31/10  
B01J 39/20  
C07B 61/00  
C07C 37/20  
C07C 39/16  
C08F 8/36  
C08L 25/08

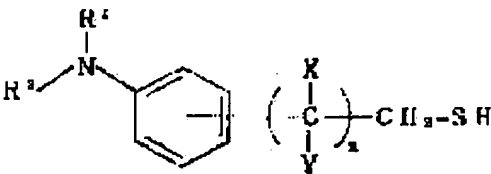
(21)Application number : 09-015213 (71)Applicant : MITSUBISHI CHEM CORP  
(22)Date of filing : 29.01.1997 (72)Inventor : KUJIRA KATSUFUMI  
WATANABE MICH  
SUZUKI TAKESHI  
SUMIYA NAOKO  
IWANE HIROSHI

(54) ION EXCHANGE RESIN AND MANUFACTURE OF BISPHENOL USING THIS RESIN

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain modified strongly acidic sulfonic acid-type ion exchange resin which shows high acetone conversion rate and good selectivity by ionic- bonding anilines having a mercapto group shown by the formula to a part of a sulfonic group of strongly acidic sulfonic acid-type ion exchange resin.

SOLUTION: The modified strongly acidic sulfonic acid-type ion exchange resin is available as a catalyst in the case of producing bisphenol A by bonding reaction of bisphenol e.g. phenol and acetone and is manufactured by ionic- bonding anilines having a mercapto group shown by the formula to strongly acidic sulfonic acid-type ion exchange resin. In the formula, R1 and R2 denote hydrogen atom, 1-4 C alkyl group or aryl group; X and Y denote hydrogen atom, 1-6 C alkyl group, 5-10 C cycloalkyl group or aryl group; (n) denotes integer of 1-3; and when (n) is 2 or 3, each of a plurality of X and Y may denote another group.



LEGAL STATUS

[Date of request for examination] 20.02.2002  
[Date of sending the examiner's decision of rejection]  
[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]  
[Date of final disposal for application]  
[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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